

## SPECIFICATION AMENDMENTS

Replace the paragraph at page 12, lines 3-10 with the following paragraph:

**FIGS. 2C and 2F** are enlarged cross-sectional views of photoresist layers 142 and ~~143~~144 formed on surfaces 122 and 124, respectively. Photoresist layers 142 and ~~143~~144 are simultaneously deposited as continuous dry films and then patterned by selectively applying light through respective reticles (not shown), applying a developer solution to remove the photoresist portions rendered soluble by the light, and then hard baking, as is conventional. As a result, photoresist layer 142 contains openings that selectively expose portions of surface 122, and photoresist layer ~~143~~144 contains openings that selectively expose portions of surface 124. Photoresist layers 142 and ~~143~~144 have a thickness of 15 microns.

Replace the paragraph at page 12, lines 11-25 with the following paragraph:

**FIGS. 2D and 2G** are enlarged cross-sectional views of various features formed in metal base 120 by wet chemical etching using photoresist layers 142 and ~~143~~144 as etch masks. In particular, the structure is dipped in a wet chemical etch that provides a front-side etch through the openings in photoresist layer 142 to the exposed portions of surface 122 and a back-side etch through the openings in photoresist layer ~~143~~144 to the exposed portions of surface 124. The structure is submerged in the wet chemical etch long enough for the etchant to etch about 120 microns into metal base 120. That is, the wet chemical etch provides a “half-etch” that removes slightly over one-half (120/200) the thickness of metal base 120 at the exposed portions. Thus, the front-side etch partially forms slot 128 and completely forms recessed portion 130, the back-side etch partially forms slot 128 and completely forms recessed portion 132, and the combination of the front-side and back-side etches completely forms slot 128. Likewise, the front-side and back-side etches are applied simultaneously, and slot 128, recessed portion 130 and recessed portion 132 are formed simultaneously. The wet chemical etch also forms the other slots 128, recessed portions 130 and recessed portions 132 as well as recessed portions 134 and the unlabeled openings and notches in a similar manner.

Replace the paragraph at page 13, lines 1-2 with the following paragraph:

**FIGS. 2E and 2H** are enlarged cross-sectional views of metal base 120 after photoresist layers 142 and ~~143~~144 are simultaneously stripped.

Replace the paragraph at page 33, line 20 to page 34, line 2 with the following paragraph:

The “upper” and “lower” surfaces of the chip and the “top” and “bottom” surfaces of the insulative housing do not depend on the orientation of the device, as will be readily apparent to those skilled in the art. For instance, the upper surface of the chip includes the pads, regardless of whether the chip is inverted, and regardless of whether the device is inverted and/or mounted on a printed circuit board. ~~Similarly, the conductive trace disposed in an opening “above” the chip includes a bottom surface that faces the upper surface of the chip, regardless of whether the chip is inverted.~~ Similarly, the terminals extend through the “bottom” surface of the insulative housing, and the leads extend through the “side” surfaces of the insulative housing, regardless of whether the device is inverted, rotated or slanted. Likewise, the device is shown with a single orientation throughout the drawings for ease of comparison between the figures, although the device may be inverted at various manufacturing stages. For instance, the device should be inverted so that the bottom surface faces upward when the epoxy paste that forms the insulative base is deposited on the structure to assist the epoxy paste with filling the remaining space in the openings in the adhesive.